

AMENDMENTS TO THE SPECIFICATION

Kindly amend the specification as follows:

[0020] Figure 4 illustrates a preferred embodiment of a system for altering a very small (e.g. micron-scale, nanometer-scale) surface area of a substrate for editing and/or repair of ICs and photomasks. The probes of the Invention can be moved into close proximity to the site proximate to the target feature using a means for maneuvering which is an apparatus that is available currently for the positioning of a scanned probe microscope (SPM). A substrate 510 to be worked rests on a movable stage 512 for initial coarse positioning of the substrate 510 and optical navigation under a high-NA (numerical aperture) objective lens microscope 514 to the site proximate to the target feature to be altered. High NA optical microscope viewing/imaging allows one to see where the apex 516 of probe 518 is relative to the feature of interest on the substrate, even if the feature of interest is below the top surface 520 of the substrate 510 (in cases when the substrate includes one or more optically transparent layers above the feature of interest).